Application Note · PlasmaQuant 9100 Elite, PlasmaQuant MS Elite



Stephen Community

Challenge

Interference-free determination of rare earth elements at trace and ultratrace levels in geological materials.

Solution

High-Resolution Array ICP-OES on PlasmaQuant 9100 Elite resolving spectral interferences and high-sensitivity ICP-MS on Plasma Quant MS Elite using a method without traditional mathematical correction of polyatomic interferences.

Analysis of Rare Earth Elements by ICP-OES and ICP-MS – Potentials and Limitations

Introduction

Contrary to their name, rare earth elements (REE) make up a substantial part of the earth's crust, where they occur dispersed among various minerals. In recent years, there has been a rising demand for REE in the fields of user electronics, catalysis, optical displays, high-performance magnets, batteries, aerospace manufacturing and medical applications. Therefore, reliable trace analysis procedures are needed in the assessment of potential mining sites, process control solutions (largely comprising of rare earth oxides, REO) and quality control of high-purity REE. Furthermore, there is a large interest from academic research in earth sciences involving trace and ultratrace level determination of REE in geology, geochemistry and mineralogy.

Quantification of REE in geological materials by Inductively Coupled Plasma Optical Emission Spectrometry (ICP-OES) is one of the most challenging analytical routines. Often containing large amounts of alumina and silica, sulfur and refractory metals, etc., the high matrix contents of digested samples require exceptional plasma robustness. This is especially the case when trace levels of REE ought to be detected and sample dilution has to be avoided. Adverse REO formation in plasma tail and severe spectral interferences due to the wealth of emission lines affect the detectability of REE by ICP-MS (Inductively Coupled Plasma Mass Spectrometry) or ICP-OES. The High-Resolution Array ICP-OES PlasmaQuant 9100 Elite is capable to overcome these barriers. With its fast-sequential echelle-double monochromatic optical bench with versatile CCD detection, it nearly doubles the spectral resolution and halves the total analysis time with respect to currently available ICP-OES instrumentation with PMT detection that is solely used for REE analysis.



ICP-MS is a popular analytical technique for the determination of REE, from raw materials including soils, rocks and ores to impurities in highly refined rare earth products. The technique offers a fast multi-element REE detection at concentrations down to the parts-per-quadrillion (ppq) range. However, challenges often faced by scientists in REE measurement include the occurrence of polyatomic and isobaric interferences that are not resolved by quadrupole ICP-MS. Collision gases can be applied to remove polyatomic interferences. With its integrated Collision Reaction Cell technology, the PlasmaQuant PQ MS Elite offers an effective solution for such requirements. Furthermore sample preparation can also impose analytical constraints and must be considered in order to obtain accurate analytical data.

Materials and Methods

For the quantification of REE, it is important that a complete digestion of the sample is achieved because any insoluble residue will result in an underestimated concentration of these elements. When acid mixtures containing hydrofluoric acid (HF) are used, insoluble fluorides of REE may remain in the precipitate. Refractory minerals such as zircon, tourmaline, chromite, rutile, garnet, spinel and corundum are decomposed incompletely by an acid attack. Decomposition by lithium metaborate and tetraborate fusion provides a complete decomposition of silicate phases and accessory minerals. However, this results in a higher amount of total dissolved solids (TDS). Since ICP-MS is typically limited to TDS levels of less than 0.3% w/v, the fusion decomposition requires additional dilution prior to analysis. For several types of geological matrices, sintering with Na₂O₂ is a very attractive analytical decomposition procedure because it is highly effective in decomposing minerals rapidly and the resulting sinter residue is easy to dissolve. Additionally, it does not introduce high concentrations of reagent elements (e.g., Li, B) that may affect future analyses [1].

Therefore, this study considered a sintering digestion in the presence of Na_2O_2 . Approximately 100 mg of sample grounded to pass a 200-mesh sieve was well mixed with 600 mg of Na_2O_2 and sintered at 480 ± 10 degrees Celsius for exactly 30 minutes in a Carbolite muffle furnace (CWF 1200) using porcelain crucibles ($30 \times 30 \text{ mm}^2$) lined with aluminum sheet. After cooling, the sinter residue was gently removed from the crucible with ultrapure water added dropwise into a 50 mL polypropylene tube. When the reaction finished, three drops of concentrated HCl and 2 mL of concentrated HNO₃ were added. The tube was filled to the mark with ultrapure water and the final solution was homogenized using a vortex stirrer.

The ICP-OES measured all samples undiluted, whereas for ICP-MS analysis, samples were diluted ten-fold with 1% HNO₃.

Samples and Reagents

- Reference Material GBW 7103
- Deionized water (>18.2 MΩ/cm, Millipore MiliQ)
- Nitric acid Supra-quality 69 % (ROTIPURAN Supra)
- Sodium peroxide (Na₂O₂) finely powdered, reagent grade, 97 % (SIGMA-ALDRICH)

Calibration

For ICP-OES, calibration solutions were prepared in a matrix-matched solution containing $12 \text{ g/L Na}_2\text{O}_2$ in $1 \% \text{ HNO}_3$. The calibration concentrations ranged from 0.1 to 1 mg/L for all elements analyzed.

For ICP-MS measurements, calibration solutions were prepared from high-purity, single and multi-element solutions (SIGMA-ALDRICH) in 1 % HNO₃ + 1.2 g/L of Na₂O₂. The calibration standards covered the concentration range from 0.25 to 25 μ g/L for La, from 0.5 to 50 μ g/L for Ce and Nd, and from 0.05 to 5 μ g/L to Pr, Sm, Eu, Gd, Tb, Dy, Er, Ho, Tm, Yb and Lu.

Instrumentation

The ICP-OES system used an HF kit for the sample introduction. Table 1 and 2 list the system configurations for ICP-OES and ICP-MS respectively.

Table 1: Configuration of the 9100 Elite, equipped with HF kit

5		
Parameter	Settings	
Plasma gas flow	15.0 L/min	
Auxiliary gas flow	1.0 L/min	
Nebulizer gas flow	0.5 L/min	
Nebulizer	Parallel path nebulizer, PFA, 1.0 L/min	
Spray chamber	PTFE cyclonic, 50 mL	
Injector	Alumina, inner diameter 2 mm	
Outer tube /Inner tube	SiAlON/alumina	
Pump tubing	PVC	
Sample pump flow	1 mL/min	
Rinse/Read delay	60 sec	
Integration time	3 sec (3 replicates)	
Plasma view	axial	

Table 2: Configuration of the PQ MS Elite

Parameter	Settings	
Plasma gas flow	9.0 L/min	
Auxiliary gas flow	1.35 L/min	
Nebulizer gas flow	0.97 L/min	
iCRC settings	No gas mode, Gas mode with Helium	
Plasma RF power	1300 W	
Dwell time	30 ms	
Scans per replicate	10	
Acquisition mode	peak hopping, 1 pt/peak)	
Number of replicates	5	
Pump rate / tubing	8 rpm, black/black PVC	
Sample uptake delay	30 s	
Stabilization time	20 s	
lon optics	Auto-optimized for highest sensitivity	

Results and Discussion

In ICP-MS, the formation of polyatomic species like MO⁺ and MOH⁺ is greatly influenced by the chemical nature of the respective element. Since oxide and hydroxide formation will follow particular stoichiometric reactions, their contribution to an analyte signal can be corrected by a fixed numerical coefficient (correction equation), determined for the specific analysis conditions. Cerium for example has a strong affinity for oxygen with oxide levels of less than 2 % being typical under optimized instrument conditions. Oxide interferences can be reduced to negligible levels by injecting a helium gas into the iCRC interference management system (Figure 1). Thus, the CRMs were investigated by ICP-MS with helium as collision gas within the iCRC. No corrections for oxide and hydroxide polyatomic interferences were applied, although isobaric interferences were accounted for.

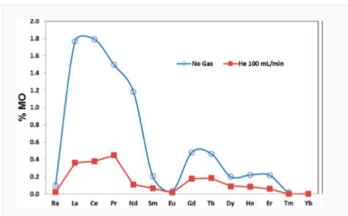


Figure 1: Oxide formation in different iCRC modes determined from single element standards

Table 3 shows the concentration values of REE in CRM GBW07103 (GSR-1) measured by HR ICP-OES and ICP-MS. Concentrations range from μ g/kg to mg/kg with excellent recoveries for both techniques used. The analysis by ICP-OES obtained RSD-values smaller than 2 % for most elements. This proves that the precision achieved with HR ICP-OES is best suited for REE-trace analysis. Moreover, the total analysis time per sample including rinse and read delays was less than 120 seconds.

Table 3: Results for CRM GBW07103 obtained by HR ICP-OES and ICP-MS

Element	CRM GBW 7103	HR ICP-OES PlasmaQuant 9100 Elit		0 Elite	ICP-MS Plasm		
	(GSR-1) Granite powder [mg/kg]	Measured [mg/kg]	Recovery [%]	MDL [mg/kg]	Measured [mg/kg]	Recovery [%]	MDL [µg/kg]
La	54 ± 4	53.4	99	0.14	60.9	113	3.5
Ce	108 ± 7	112	104	0.85	114	106	0.9
Pr	12.7 ± 0.8	12.2	96	1.55	13.2	104	0.6
Nd	47 ± 4	48.6	103	0.34	51.2	109	2.6
Sm	9.7 ± 0.8	9.23	95	0.65	10.6	108	2.7
Eu	0.85 ± 0.07	0.71	84	0.04	0.82	96	2.7
Tb	1.65 ± 0.09	n.a.*			1.68	102	0.8
Gd	9.3 ± 0.7	10.3	111	0.36	9.69	104	1.4
Dy	10.2 ± 0.4	10.6	104	0.32	10.8	106	0.4
Er	6.5 ± 0.3	7.0	108	0.15	7.01	108	0.3
Но	2.05 ± 0.17	2.22	108	0.11	2.24	109	1.6
Tm	1.06	n.a.*			1.11	105	0.8
Yb	7.4 ± 0.5	7.67	104	0.34	8.23	111	1.5
Lu	1.15 ± 0.09	1.11	97	0.19	1.17	102	0.4

^{*} this element was not analyzed by ICP-OES.

The unique potential of the PlasmaQuant 9100 Elite becomes even clearer when inspecting the Nd/Ce-line pair at about 401.2 nm (Figure 2). With a line spacing of only 14 pm, the Nd 401.225 nm (red) is severely overlapping with Ce 401.239 nm (blue) in conventional ICP-OES systems and thus only a high-resolution ICP-OES can resolve the individual lines for analysis. The Nd 401.225 nm is the most sensitive Neodymium line and hence optimal for trace analysis.

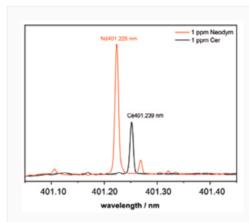


Figure 2: HR ICP optical emission spectra of the Nd 401.225 (red) and the Ce 401.239 nm line (blue) as in the highest calibration standard. The green line shows the automatic baseline correction (ABC) of the Nd spectrum.

Conclusion

For the analysis of REE in geological samples, ICP-OES and ICP-MS are ideal analytical techniques because of the multielement detection capabilities. However, line-rich emission spectra and isotope-rich mass spectra plus polyatomic interferences from e.g., oxides require highest performance and high-end technological solutions to meet today's requirements. ICP-MS with its high detection power is an ideal technique, especially since collision cell techniques help to eliminate interferences. The improvements made during the last decade to make the instruments reliable and easy to use for routine applications are the reason for the wide acceptance of this technology. The high-detection power especially for REE allows detection limits in the ppt to ppb range. However, limited matrix tolerance and complex optimization of many parameters still require an experienced operator to reach the full performance of this technique.

ICP-OES systems are robust and reliable instruments used as a workhorse in many analytical laboratories. Improved optics and detector designs led to much lower detection limits over the past years. High-resolution instruments make it possible to use typically interfered lines, making them ideally suited for the analysis of complex matrices. The easier handling and robust introduction system allow for analysis without previous sample dilution. This leads to an instrument performance that fits for many applications.

Table 4 presents a summary of potentials and limitations for both techniques. Each ICP technique shows strengths and weaknesses. Less matrix tolerance and higher running costs compensate for the better detection limits of ICP-MS. The robustness and higher matrix tolerance of ICP-OES comes with more frequent cleaning and careful configuration of the sample introduction system.

Table 4: Comparison of potential and limitations for ICP-OES and ICP-MS

PlasmaQuant 9100 Elite HR-ICP-OES	Potential / Limitations	PlasmaQuant MS Elite ICP-MS
TDS >30 % are toleratedDirect analysis	Heavy matrix (fusion or acid digest)	TDS typically <0.3 %Dilution strategies required
Overlap of emission linesHigh resolution requiredMathematical correction tools used	Spectral Interferences	 Molecular interferences e.g. REO Correction equations used Interference management systems required
mg/L or mg/kg (ppm _w)	Detection limits (DL)	 μg/L or μg/kg (ppb_w)
RSD typically < 3 % for REERecovery typically ± 5 % for REE	Precision	RSD typically < 1 % for REERecovery typically ± 2 % for REE
High resolution with CCDTTime saving single line evaluation with automated algorithms	Throughput	 High sensitivity allows short dwell times Fast wash-out using discrete sample introduction
 Workhorse for REE analysis with mg/kg detectability 	Performance	 Advanced analytical capabilities incl. high- purity REE, isotope ratio analysis and μg/kg detectability
 Direct analysis Quick method development Robust system (sealed optic) Easy maintenance (cleaning) 	Handling	 Dilution strategies High operator skills More prone to contaminations Frequent cleaning required
 Lower cost of technology Glassware (consumables) Normal chemicals Less stringent lab requirements 	Cost of Ownership	 High costs of technology Consumables (cones, glassware) High purity chemicals High lab standard

The comparison shows the high performance of both analytical techniques for the analysis of REE in geological samples. The PlasmaQuant 9100 Elite and the PlasmaQuant MS Elite offer outstanding features to overcome the challenges in the analysis of REE. Interference removal by either the high-resolution optical system or collision cell technology (iCRC) in combination with low gas consumption underline the high performance of these instruments.

References

[1] Meisel, T. et al.; Geostandard Newslett. 2002, 26, 53-61

This document is true and correct at the time of publication; the information within is subject to change. Other documents may supersede this document, including technical modifications and corrections.

Headquarters

Analytik Jena GmbH Konrad-Zuse-Strasse 1 07745 Jena · Germany Phone +49 3641 77 70 Fax +49 3641 77 9279 info@analytik-jena.com www.analytik-jena.com Version 1.0 | Author: SeWu en · 12/2020 © Analytik Jena GmbH | Pictures ©: Pixabay/Engin Akyurt